	Hits	Search Text	DBs	Time Stamp
1	6	((mask?less) (without near2 mask) mask) near3 pattern same (electrons electron particle particles cell cells) and substrate and stress near2 dielectric and dielectric with (interconnect conductor conductive conduction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/01/06 16:42
2	20	((mask?less) (without near2 mask) mask) near3 pattern same (electrons electron particle particles cell cells) and substrate and stress with dielectric and dielectric with (interconnect conductor conductive conduction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/01/06 16:46
3	6	exposure adj (cell cells) and dielectric with (interconnect conductor conductive conduction) and lithograph$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/01/06 16:47
4	29	exposure adj (cell cells) and dielectric with (interconnect conductor conductive conduction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/01/06 16:48
5	0	(maskless adj lithograph$3 and (cell cells) with expose$4 and dielectric with (interconnect conduct$4)).clm.	US-PGPUB; USPAT	2007/01/06 17:37
6	11	(maskless with lithograph$3 and (cell cells) with expose$4 and dielectric with (interconnect conduct$4)).clm.	US-PGPUB; USPAT	2007/01/06 17:38

	Hits	Search Text	DBs	Time Stamp
7	0	(direct adj write with lithograph$3 and (cell cells) with expose$4 and dielectric with (interconnect conduct$4)).clm.	US-PGPUB; USPAT	2007/01/06 17:38
8	0	(direct adj write and lithograph$3 and (cell cells) with expose$4 and dielectric with (interconnect conduct$4)).clm.	US-PGPUB; USPAT	2007/01/06 17:39
9	0	(direct adj write and lithograph$3 and (cell cells) with expose$4).clm.	US-PGPUB; USPAT	2007/01/06 17:39
10	0	(direct adj write and lithograph$3 and (cell cells) and expose$4).clm.	US-PGPUB; USPAT	2007/01/06 17:39
11	85	(direct adj write and lithograph$3).clm.	US-PGPUB; USPAT	2007/01/06 17:45